

Maximizing CCC and the March to an Unburnable Probe



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Agenda

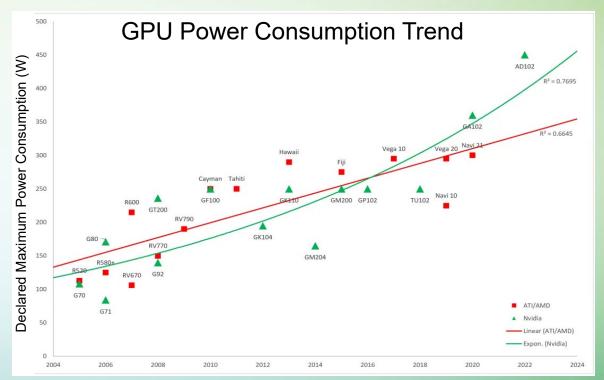
- Why Does CCC matter?
- Hybrid Probe Review
- Next Generation Probe Review
- Metallized Guide Plate Review
- Maximized CCC Conclusion





Industry Trends

- High Performance Compute and GPU applications are marching to 1kW devices (1,000A at 1V)
 - Currently shipping 400A devices today (400W at 1V)
 - Newest HPC devices have >50 Billion Transistors
- New nodes and technology advancements are creating downward pressure on yield
 - Yield drop with each node transition
 - Transitions to more complex digital coms (PAM4) decrease yield
 - Larger die for HPC and GPU applications are lowering wafer yield
- As yields decrease and as device power increases Probe Card capability and CCC must increase



https://www.techspot.com/article/2540-rise-of-power/



CCC Terminology

Current Carrying Capability

 The amount of current that a probe or spring can withstand before burning or damage occurs

• ISMI CCC

Current applied where a 20% lower force is observed in a probe (spring)

MAC (Maximum Allowable Current)

Current applied where a change in probe force or planarity is first observed

ECCC (Effective Current Carrying Capability)

- An averaging of total current that a group of probes can withstand before burning occurs

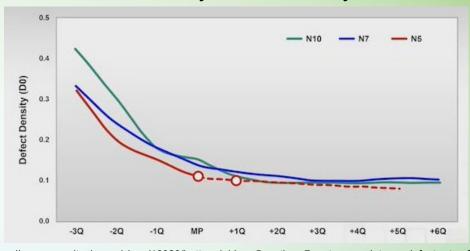




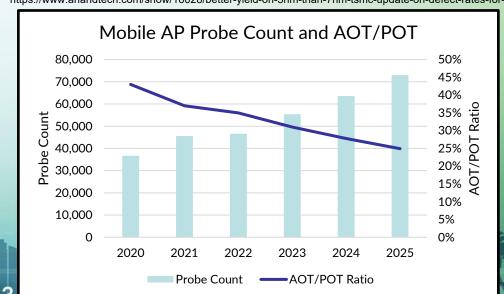
Why Does CCC Matter?

- Probe Current Carrying Capability prevents probe burning when something goes wrong during wafer testing
 - Shorts in the DUT
 - Unstable contact between the DUT and Probe card
- High CCC Probes improves uptime and MTBF as the probe card becomes more robust and resistant to probe burning

Defect Density over Time by Node



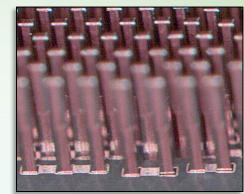
https://www.anandtech.com/show/16028/better-yield-on-5nm-than-7nm-tsmc-update-on-defect-rates-for-n5



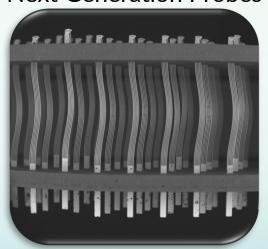


Methods for Improving CCC

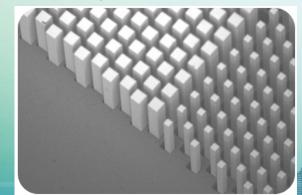
Metallized Guide Plates



Next Generation Probes



Hybrid Probes







Hybrid Architecture

- SOCs have PWR/GND in the middle of the Device and I/O in the periphery of the Device
 - PWR/GND typically at ≥150um pitch
 - Can use wider, high CCC probes
 - I/O typically at ≤90um pitch
 - Can use smaller, lower CCC probes
- By combining probe types in the Probe Card the Effective CCC is increased



Hybrid Increasing Available CCC

FFI Hybrid probe technology increases probe card available CCC

 combining tight pitch low CCC probes and wide pitch High CCC probes in the same design

Product A as a test case

- Min Pitch = 90um
- Requires MF100F for 90um pitch with CCC of 1,200 mA
- If hybrid is used available CCC can be improved by 20% to 1,435 when using MF130/MF100

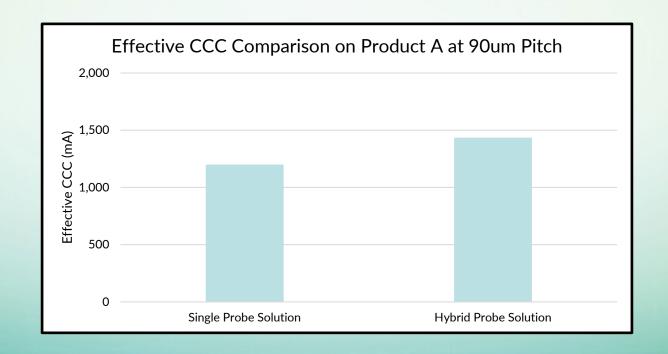
Product A x8 Hybrid Available CCC Example		
Hybrid Probe Type	MF100F	MF130F
CCC (mA)	1,200	1,500
Probe Count	4,216	15,248
Total CCC (mA)	5,059,200	22,872,000
Total Probe Card Available CCC (mA)	1,435	
% Improvement over Single Probe (MF100)	20%	





Maximizing Effective CCC

Hybrid probes provide 20% higher effective CCC relative to single probe solutions

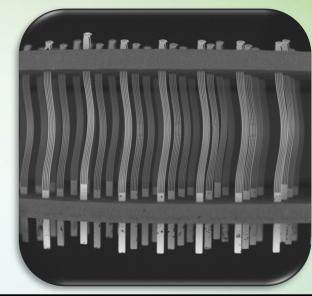


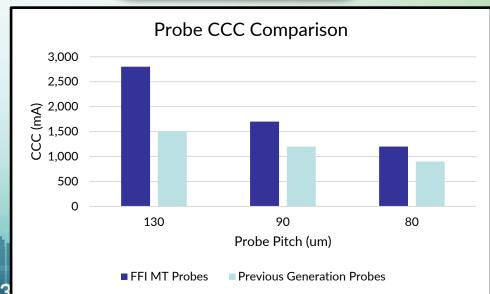




FFI MT Probe

- MT next generation probes provide
 >50% improved CCC over current gen. MEMS probes
- Higher speed performance with shorter probe length.
- Hybrid compatible MT probe family to further enhance CCC and highspeed capability.
- Metallized Guide Plate can further increase effective CCC to >3A

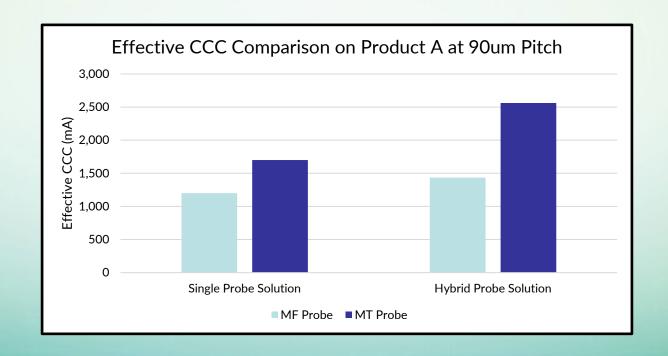






Maximizing Effective CCC

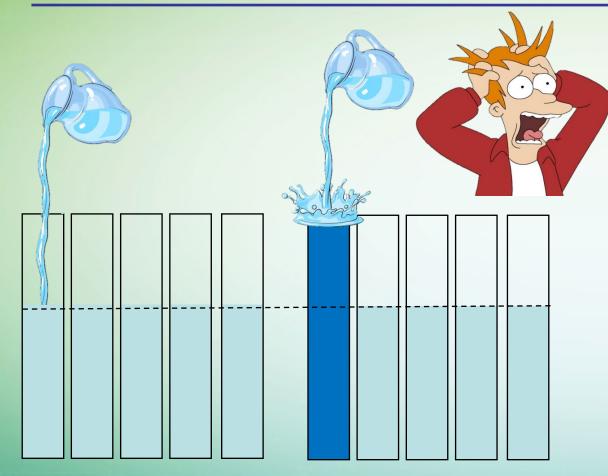
- Hybrid probes provide 20% higher effective CCC relative to single probe solutions
- MT Probes provide 42% higher CCC relative to last generation probes
 - 78% improvement when combined with Hybrid



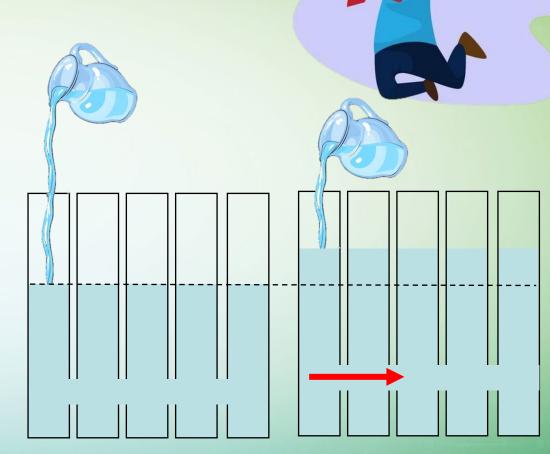




What is Metallized Guide Plate? (Analogy)







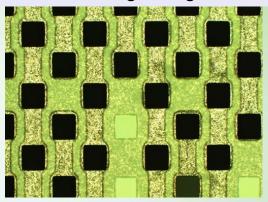
Distributed (MeGP)



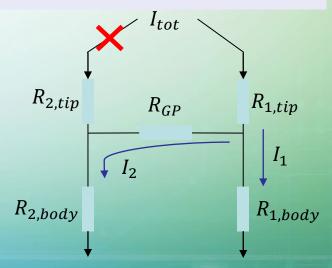
What is Metallized Guide Plate?

- Metallized Guide Plates (MeGP) connect
 VDD and GND nets together through
 metal patterns on the Guide Plate
 - Provides alternative current path when overcurrent events occur
 - Enables Improved Contact with the DUT through alternative current paths

Metallization High Magnification

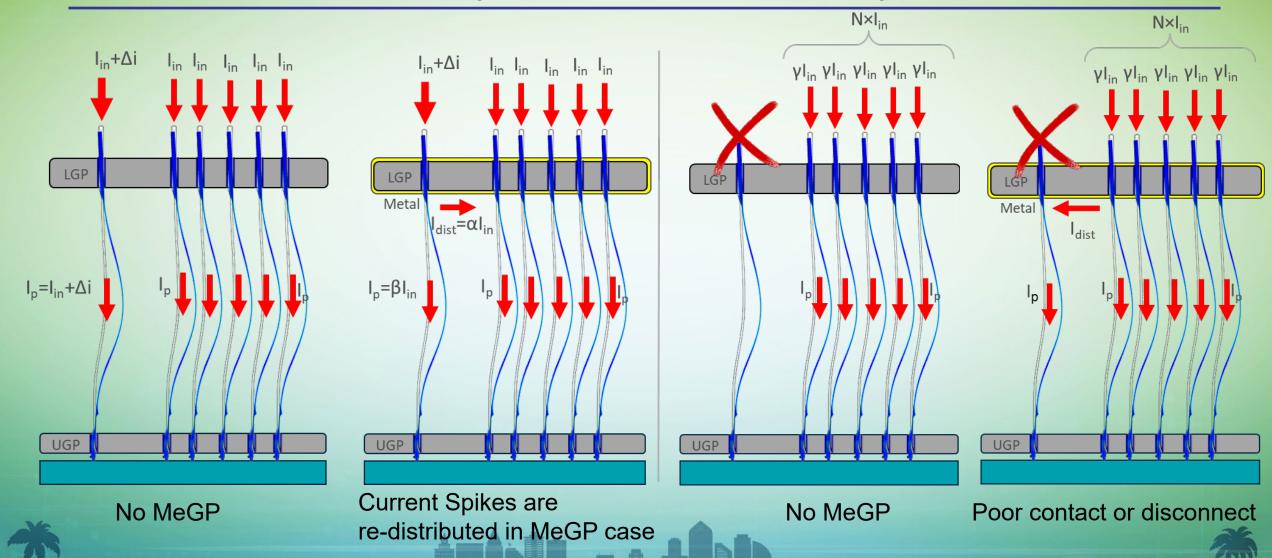


Metallization 2-Probe Circuit



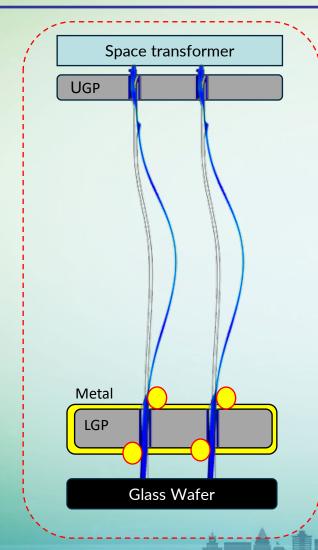


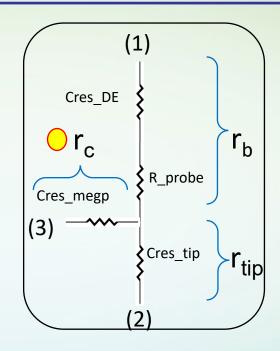
Examples of how MeGP can help





MeGP Technical Terminology





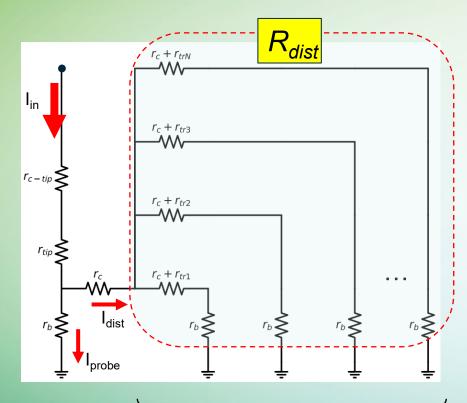
r_b: Probe body + DE Cres

or_c: Tip-MeGP Contact resistance

r_{tr}: Trace resistance



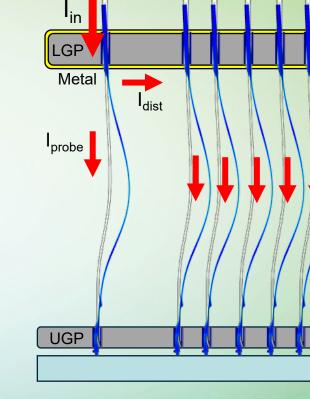
Generalized MeGP Effective CCC model (building block)



 $R_{dist} = \left(\sum_{n=1}^{N} \frac{1}{r_c + r_{tr(n)} + r_b}\right)$

$$ECCC = I_{probe} \left(1 + \frac{r_b}{r_c + R_{dist}} \right)$$
amplification factor

Effective CCC



r_b: Probe body + DE Cres

r_c: Tip-MeGP Contact resistance

r_{tr}: Trace resistance

N: Number of probes

R_{dist}: resistance of distributed network





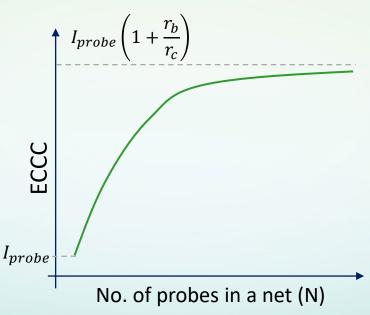
Effect of trace resistance and number of probes

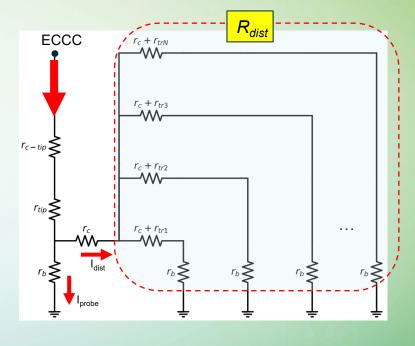
(1) If $r_{tr} \ll r_c + r_b$, the CCC will be layout independent, and the general equation reduces to:

$$ECCC_{1} = I_{probe} \left(1 + \frac{r_{b}}{r_{c} + \frac{r_{c} + r_{b}}{N}} \right)$$

(2) For large gang numbers, N, the equation reduces to:

$$ECCC_2 = I_{probe} \left(1 + \frac{r_b}{r_c} \right)$$





$$1 + \frac{r_b}{r_c}$$

 $1 + \frac{r_b}{l}$ is the best CCC amplification factor one can get.

rb: Probe body + DE Cres

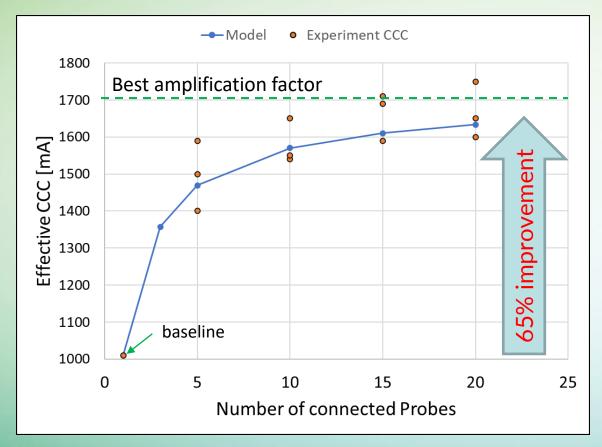
rc: Tip-MeGP Contact resistance

rtr: Trace resistance

N: Number of probes



Validation using measured CCC and True MeGP CRES data



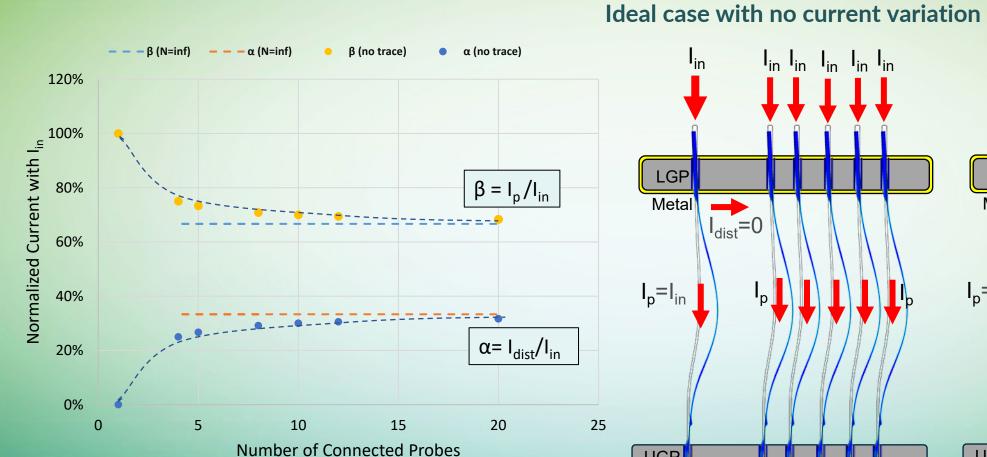
Effective CCC
$$ECCC = I_{probe} \left(1 + \frac{r_b}{r_c + R_{dist}} \right)$$
 amplification factor

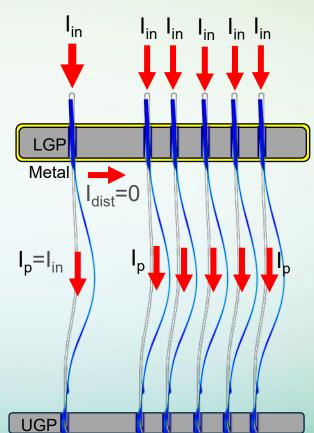
- Excellent agreement between model and experiment was achieved.
- **©** ECCC showed a 65% average improvement for 20 connected probes.

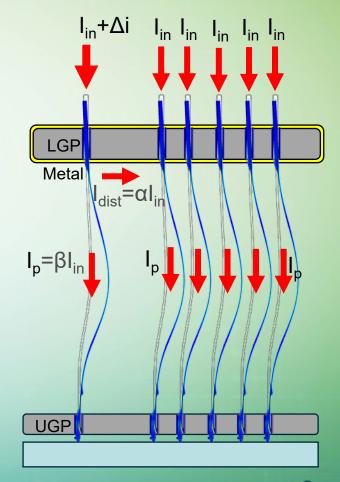




Model Extension to real cases - Current Spike events



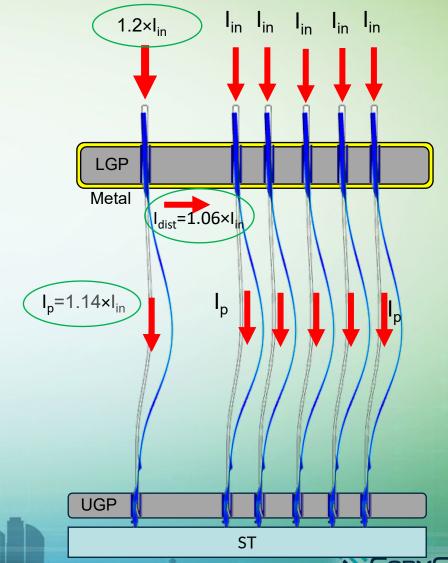




Current spike event

Numerical example

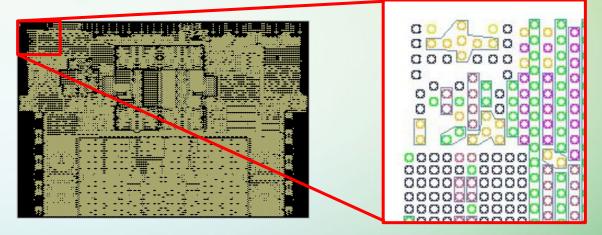
- For a 20-ganged probes with negligeable trace resistance, $\alpha = 32\%$ and $\beta = 68\%$.
- A 20% increase in nominal current (lin), translates to 6.4% increase in l_{dist} and 13.6% in l_{probe}.



MeGP Design Challenges

- Challenge: Design of the MeGP is difficult due to the number of nets and probes involved.
 - A design error could be fatal in the yield of the MeGP leading to shorts from VDD to GND
 - Design complexity could significantly
- Solution: Automated Design and DFM rule implementation
 - Eliminates mistakes from manual design
 - Decreases design cycle time to a few hours

Design Automation Improves Design Cycle
Time and Reduces Errors

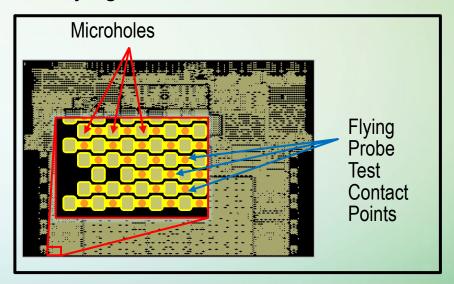




MeGP Verification Challenges

- Challenge: MeGP needs to be verified for shorts before stitching the probes and completing assembly of the Probe Card
 - POR process flow verifies electrical continuity with PRVX
 - If short is found the Probe Head would need to be disassembled and fixed
 - Long Cycle times at the last step of the manufacturing process
- Solution: Implementation of Flying Probe Test after MeGP Plating
 - Allows rework of GPs if needed
 - Ensures high quality through manufacturing process

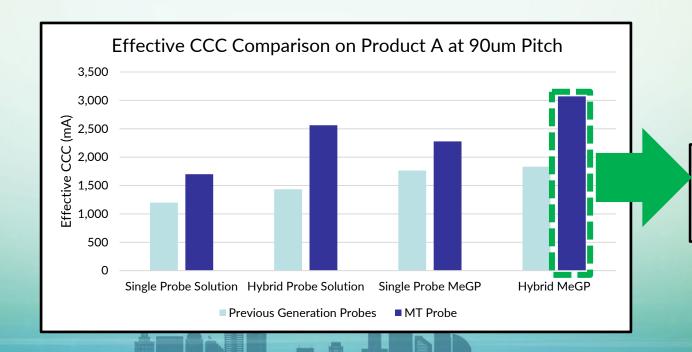
Flying Probe Test Contact Points





Maximizing Effective CCC

- MeGP Improves Effective CCC by 65% depending on the probe architecture
- FFI has achieved the first >3A CCC Probe card at 90um pitch using Next generation MT Probes, Hybrid probes, and Metallized Guide Plate
 - Short Cycle Time and Excellent quality guaranteed through Design Automation and Outgoing Flying Probe Test



MT Hybrid with MeGP provides Best Effective CCC > 3A







Thank You!!



